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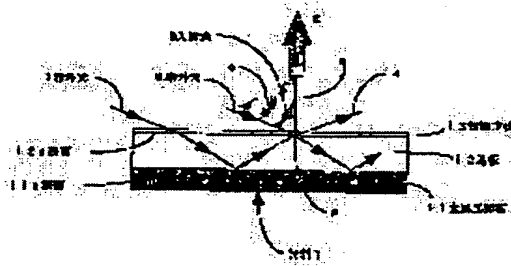
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OTSUKA YOSHIKAZU**(54) METHOD FOR MEASURING HIGHLY SENSITIVE REFLECTED INFRARED SPECTRUM AND SAMPLE FOR MEASUREMENT**

(57)Abstract:

PROBLEM TO BE SOLVED: To achieve quantitative analysis of the orientation or the light of molecules of an object to be measured in an interface between the object to be measured and various base material using highly sensitive reflected infrared spectroscopy.

SOLUTION: A substrate 12 transmitting infrared rays at a rate of 1-100% is formed at a thickness of 0.1-3 μ m on a mirror finished surface 11a of a metal reflecting plate 11 for reflecting infrared rays to make a sample 1 in which a 1-200nm thick thin film-like object 13 to be measured is formed on the surface 12a of the substrate 12. Then, either P-polarized infrared rays or S-polarized infrared rays or both thereof are admitted into the sample 1 from the side of the object 13 to be measured to measure the spectrum of the infrared rays 4 reflected from the sample 1.

**LEGAL STATUS**

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